

Notice of References Cited	Application/Control No. 10/756,122		Applicant(s)/Patent Under Reexamination YAU ET AL.	
	Examiner Julio J. Maldonado		Art Unit 2823	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,970,376	10-1999	Chen, Chao-Cheng	438/637
*	B	US-6,348,421 B1	02-2002	Shu et al.	438/788
*	C	US-5,817,572	10-1998	Chiang et al.	438/624
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	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Shu et al., Producing a Thin Film Having a Low Dielectric Constant Using HDP-CVD, Patent Application 09/019,900, page 3, line 25 - page 4, line 1 and page 14, lines 9 - 22.
	V	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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